

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

n re Application of:

Ito, et al.

Serial No.: 10/630,293

Confirmation No.: 9715

Filed:

July 30, 2003

For:

Ion Implantation Method,

SOI Wafer

Manufacturing Method And Ion Implantation

System

MAIL STOP AMENDEMENT Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Group Art Unit: 2823

Examiner: George R. Fourson III

CERTIFICATE OF MAILING 37 CFR 1.8

I hereby certify that this correspondence is being deposited on the control of th

Date /18/05

Signature 2

RESPONSE TO RESTRICTION REQUIREMENT DATED DECEMBER 20, 2004

In response to the Restriction Requirement dated December 20, 2004, having a shortened statutory period for response set to expire on January 20, 2005, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/SOEI/0057/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Specification begin on page 2 of this paper. Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper. Remarks/Arguments begin on page 7 of this paper.